

**HIP TREATMENT FOR PLASMA-SPRAYED CERAMIC FILM**

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**Abstract of JP 2301550 (A)**

**PURPOSE** To improve the corrosion resistance and thermal shock resistance of a sprayed deposit by allowing temp. rise and pressure rise to proceed simultaneously in a reducing atmosphere at the time of subjecting a plasma-sprayed ceramic film to HIP treatment by a capsule free method.

**CONSTITUTION** A ceramic film is formed by means of plasma spraying. Subsequently, temp. rise and pressure rise are allowed to proceed simultaneously in a reducing atmosphere, and HIP treatment by a capsule free method is applied to the above film, by which the open pores in the film are formed into closed pores. By this method, the thermal shock resistance and corrosion resistance of the film can be improved.

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